



# Products For Improved Wafer Processing

## Product: **SCA –Water Rinse Aid**

Surface Cleaning Agent for slurry removal after wire saw processing

### Product Description:

- water-based concentrate
- non-foaming and odorless
- biodegradable and environmentally friendly
- economical to use
- effective in dilution levels up to 100:1

### Major Markets:

- Solar, Semiconductor, Optical

### Benefits:

- Faster water rinsing, hence reduced re-deposition of slurry solids on wafer surface
- Superior wafer surface wetting characteristics
- Reduced wafer damage caused by particle deposition / coagulation, hence lower wafer breakage on separation
- Applicable to all types of water rinse stations (spray, bath, Weir)
- Improved overall wafer yield

For product evaluations, information, and sample, please contact:

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